

FORM PTO-1449
INFORMATION DISCLOSURE
STATEMENT BY APPLICANT

Complete if Known

Application No.	10/566,849
Filing Date	May 9, 2006
First Named Inventor	Karl-Heinz Schuster
Art Unit	2851
Examiner Name	Steve Whitesell
Attorney Docket No.	SHN-146-A

U.S. Patent Documents

Examiner INITIALS	Cite No. ¹	Document No. Number-Kind Code ² (If Known)	Publication Date mm-dd-yyyy	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		us-2005/0219707	10-06-2005	Schuster et al.	
		us-2005/0225737	10-13-2005	Weissenrieder et al.	
		us-2006/0221582	10-05-2006	DeNies et al.	
		us-2005/0190455	09-01-2005	Rostalski et al.	
		us-2005/0179877	08-18-2005	Mulkens et al.	
		us-2003/0174408	09-18-2003	Rostalski et al.	
		us-2002/0163629	11-07-2002	Switkes et al.	
		us-2005/0161644	07-28-2005	Zhang et al.	
		us-2005/0117224	06-02-2005	Shafer et al.	
		us-2004/0105170	06-03-2004	Krahmer et al.	
		us-2005/074704	04-07-2005	Endo et al.	
		us-2005/0068499	03-31-2005	Dodoc et al.	
		us-2005/0024609	02-03-2005	De Smit et al.	
		us-4,346,164	08-24-1982	Tabarelli et al.	
		us-4,890,903	01-02-1990	Treisman et al.	
		us-5,446,591	08-1995	Medlock, Kevin	
		us-5,682,263	10-1997	Robb et al.	
		us-6,181,485	01-2001	He, Chuan	

FOREIGN PATENT OR PUBLISHED PATENT APPLICATION

DOCUMENT NO.	PUBLICATION DATE	COUNTRY OR PATENT OFFICE	CLASS	SUBCLASS	TRANSLATION
WO2005/059617	06-30-05	PCT			
WO2006/045748	05-04-06	PCT			
WO2005/006026	01-20-05	PCT			
WO2005/081067	09-01-05	PCT			
WO2005/059645	06-30-05	PCT			
WO2005/059618	06-30-05	PCT			
WO2004/019128	03-04-04	PCT			
WO2005/031823	04-07-05	PCT			
EP 1522894A2	04-13-05	EP			
EP 1486827	12-15-04	EP			

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, etc.)

International Search Report dated 31 May 2005

"LIQUID IMMERSION DEEP-ULTRAVIOLET INTERFEROMETRIC LITHOGRAPHY", J.A. Hoffnagle, W.D. Hingsberg, M. Sanchez and F.A. Houle, Journal of Vacuum Science & Technology B: Microelectronics Processing and Phenomena, American Vacuum Society, New York, NY, U.S., Vol. 17, No. 6, November 1999 (1999-11) pp 3306-3309, XPO12007924, ISSN: 0734-211X, pp 3307-3308, NA+1.2, $n(\text{prism})=1.5 < n(\text{immersion})=1.51$

XP-0023300789 "WATER-BASED 193nm IMMERSION LITHOGRAPHY" Online!, Bruce Smith, 28 January 2004 (2004-01-28), XP 002329291 retrieved from the Internet:
URL: <http://www.sematech.org/resources/litho/meetings/immersion/20040128/presentations/06%20ri%20microstepper%20efforts%20Smith.pdf> retrieved on 2005-05-24, p. 14: NA>1.1 lens material: SiO2, p. 22: $n(\text{liquid lens}) > 1.6 > n(\text{SiO2})$

EXAMINER

/Steven Whitesell/Gordon/

DATE CONSIDERED

07/01/2008

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not considered. Include a copy of this form with next communication to applicant.

ALL REFERENCES CONSIDERED EXCEPT WHERE LINED THROUGH. /S.W./